

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant	:	Yamazaki et al.
Appl. No.	:	10/566,425
Filed	:	January 30, 2006
For	:	POSITIVE RESIST COMPOSITION AND METHOD OF FORMING RESIST PATTERN
Examiner	:	Chu, John S Y
Group Art Unit	:	1795

**AMENDMENT AND RESPONSE TO OFFICE ACTION****Mail Stop Amendment**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

In response to the Office Action mailed **March 23, 2009**, please consider the following amendments and remarks:

**Amendments to the Claims** begin on page 2 of this paper.

**Remarks** begin on 5 of this paper.